

21. (Amended) An apparatus for surface treatment comprising:
a processing vessel in which an object to be processed is placed;
means for supplying ClF_3 gas into the processing vessel;
means for activating the ClF_3 gas supplied in the processing vessel; and
means for supplying a reducing gas into the processing vessel.

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22. (Amended) An apparatus for surface treatment comprising:
a processing vessel in which an object to be processed is placed;
means for supplying ClF_3 gas into the processing vessel;
means for promoting adhesion of ClF_3 gas to the object to be processed; and
means for activating ClF_3 gas supplied in the processing vessel.

5 23. (Amended) An apparatus for surface treatment according to claim 22,
further comprising a mount located in the processing vessel for setting the object to be
processed thereon.

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24. (Amended) An apparatus for surface treatment according to claim 23,
wherein the means for promoting adhesion of the ClF_3 gas to the object to be processed
is provided in (the) mount for cooling the object to be processed on (the) mount.

25. (Amended) An apparatus for surface treatment according to claim 24,
wherein the means for activating the ClF_3 gas heats the object to be processed in a
heating position at a distance from an object setting position for setting the object on (the)
mount.

26. (Amended) An apparatus for surface treatment according to claim 25, further comprising means for elevating and lowering the object to be processed between the object setting position and the heating position.

27. (Amended) A cluster device comprising:
the apparatus for surface treatment according to claim 21, further comprising:
a transport chamber for maintaining a non-reactive atmosphere therein and for transporting an object to be processed in the non-reactive atmosphere to and from the surface processing apparatus; and
at least one processing apparatus for transporting the object to be processed to and from the transport chamber.

Please add new claims 29-32 as follows:

29. (New) An apparatus for surface treatment comprising:
a processing vessel into which an object to be processed is placed;
means for supplying chlorine-containing gas into the processing vessel;
means for activating the chlorine-containing gas supplied into the processing vessel; and
means for supplying a reducing gas into the processing vessel.

30. (New) A cluster device comprising:
the apparatus for surface treatment according to claim 29, further comprising:
a transport chamber for maintaining a non-reactive atmosphere therein and for transporting an object to be processed in the non-reactive atmosphere to and from the apparatus for surface treatment; and

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at least one processing apparatus for transporting the object to be processed to and from the transport chamber. *dim?*

31. (New) An apparatus for surface treatment comprising:

a processing vessel into which an object to be processed is placed;

means for supplying cleaning gas into the processing vessel;

means for promoting adhesion of cleaning gas to the object to be processed; and *cool*

means for activating cleaning gas supplied in the processing vessel. *Heat*

32. (New) A cluster device comprising:

the apparatus for surface treatment according to claim 31, further comprising:

a transport chamber for maintaining a non-reactive atmosphere therein and for transporting an object to be processed in the non-reactive atmosphere to and from the surface processing apparatus; and

at least one processing apparatus for transporting the object to be processed to and from the transport chamber.

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